
Equipment & Materials Integration Challenges

**American Vacuum Society CMP User Group
December 3, 2003
Sunnyvale, CA**

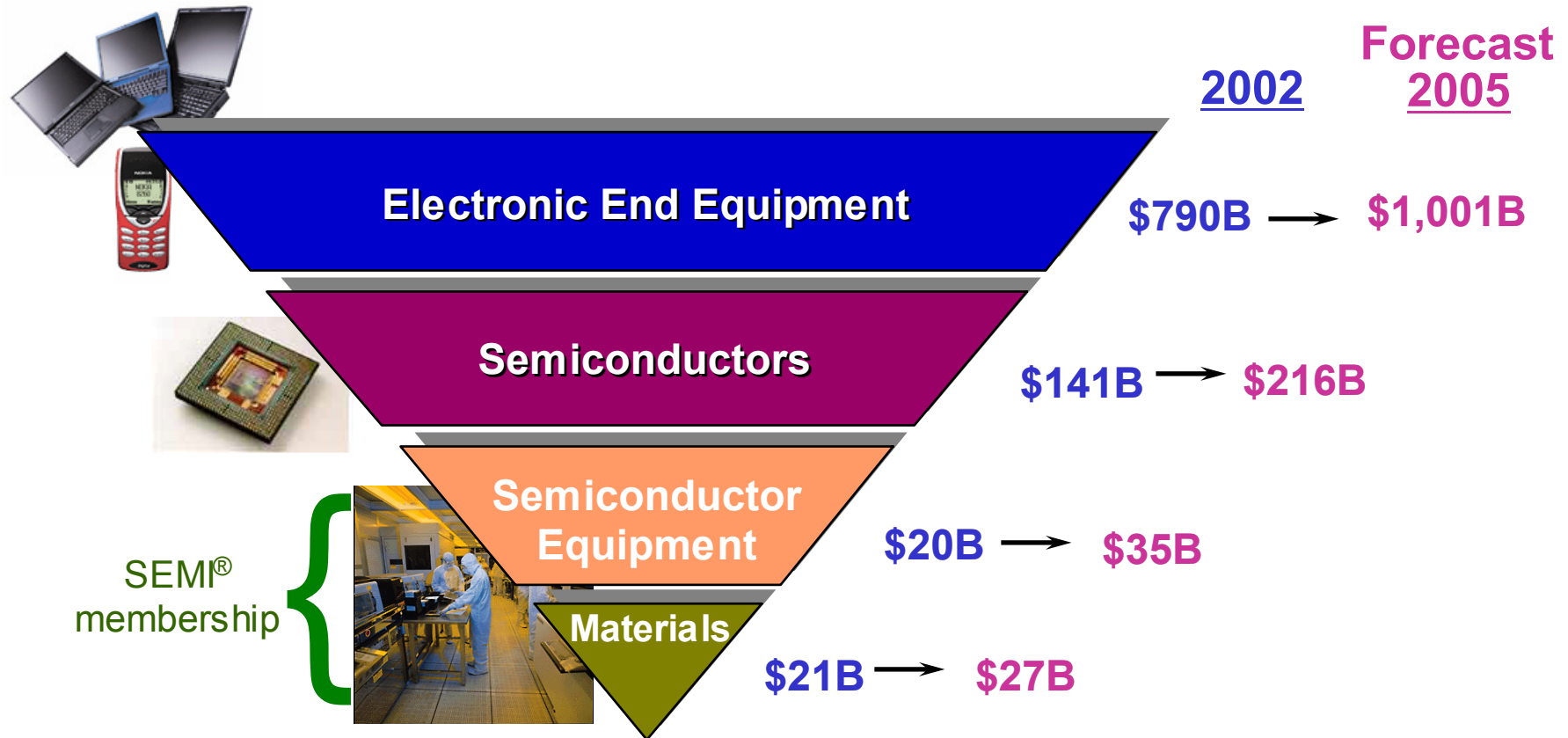
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Industry Research and Statistics
SEMI**



Outline

- Materials & Equipment Markets**
- Emerging Technologies**
- Interconnect Integration Challenges**
- Summary**

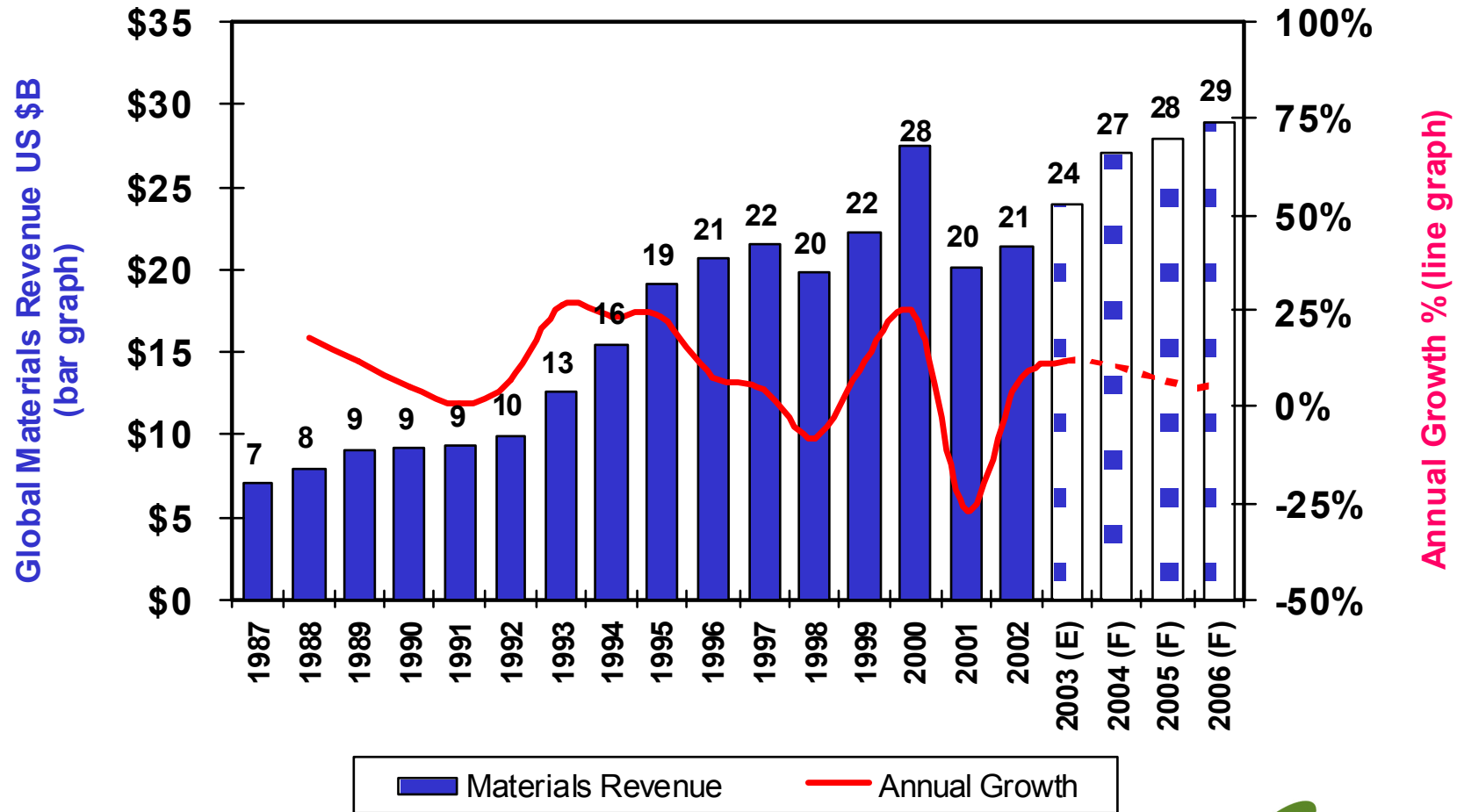
The Electronics Ecosystem



Source: SEMI, SIA/WSTS October 2003, Henderson Ventures November 2003



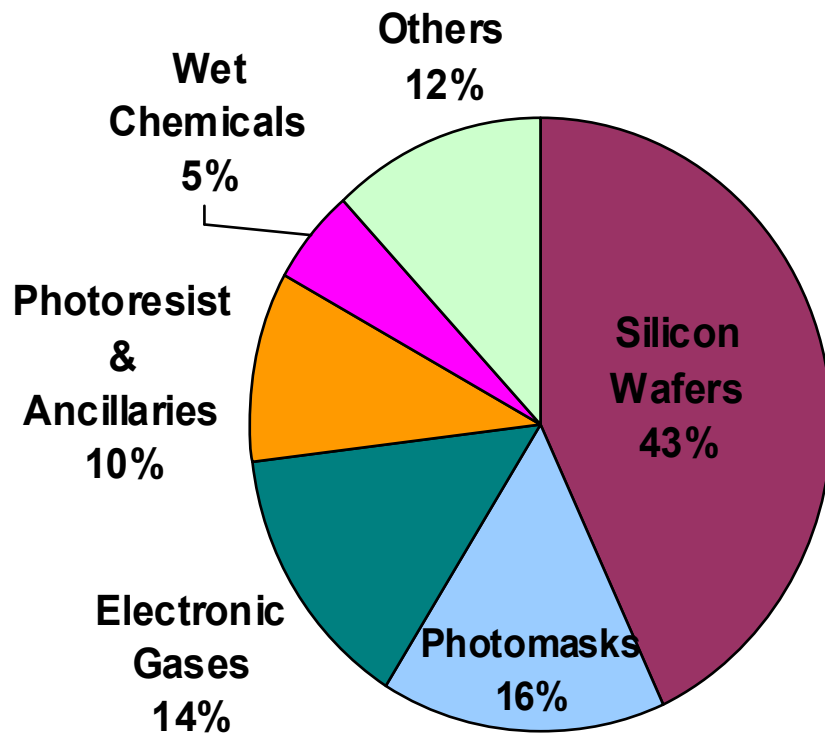
Electronic Materials Cycles



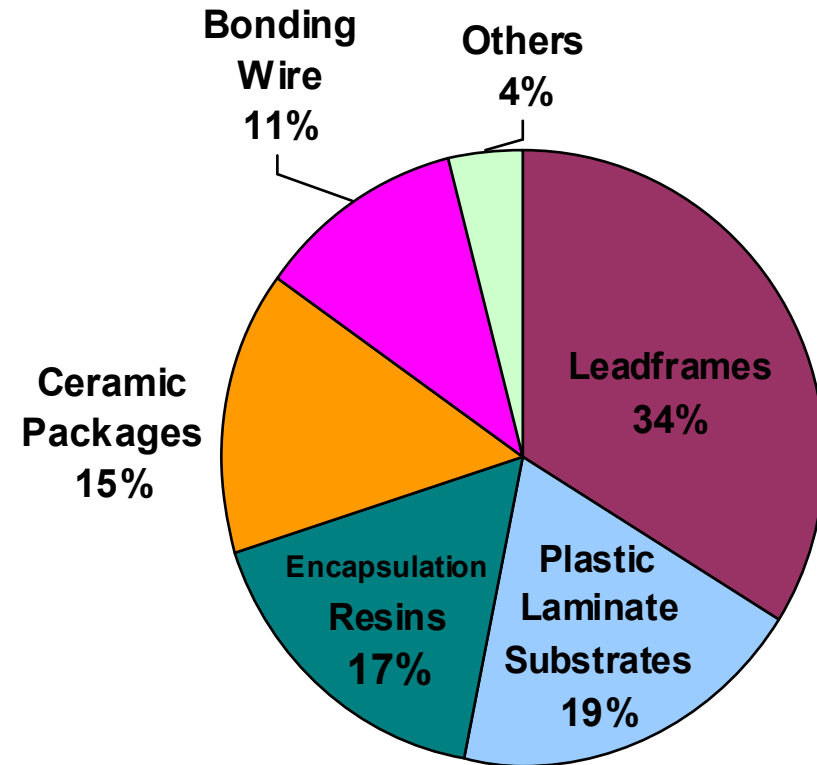
Source: Rose Associates historical reports, SEMI



2002 Global Materials Markets



2002 Global Wafer Fab Materials \$12.98B



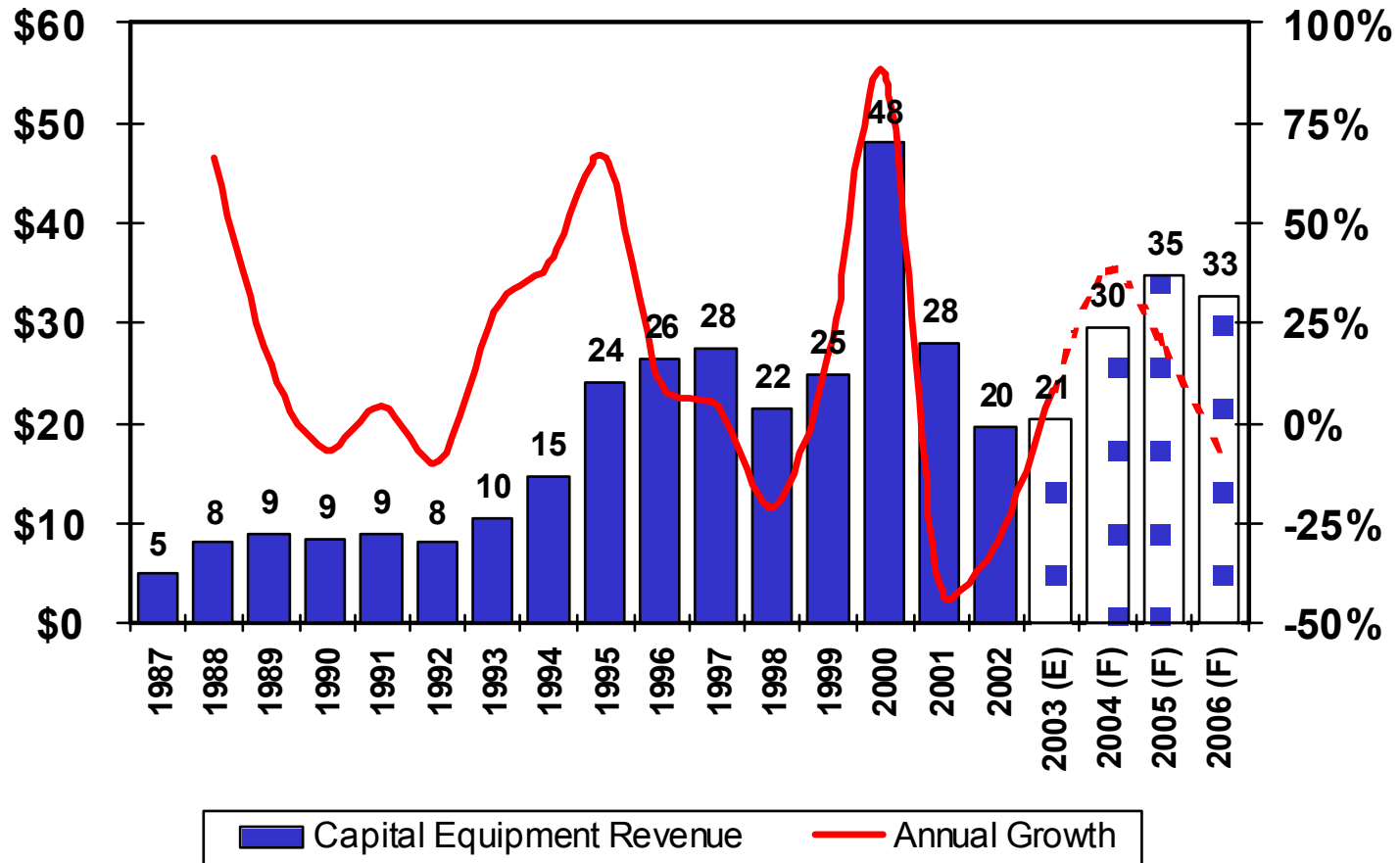
2002 Global Package Materials \$8.41B

Source: SEMI March 2003



Capital Equipment Cycles

Global Capital Equipment Revenue US \$B
(bar graph)

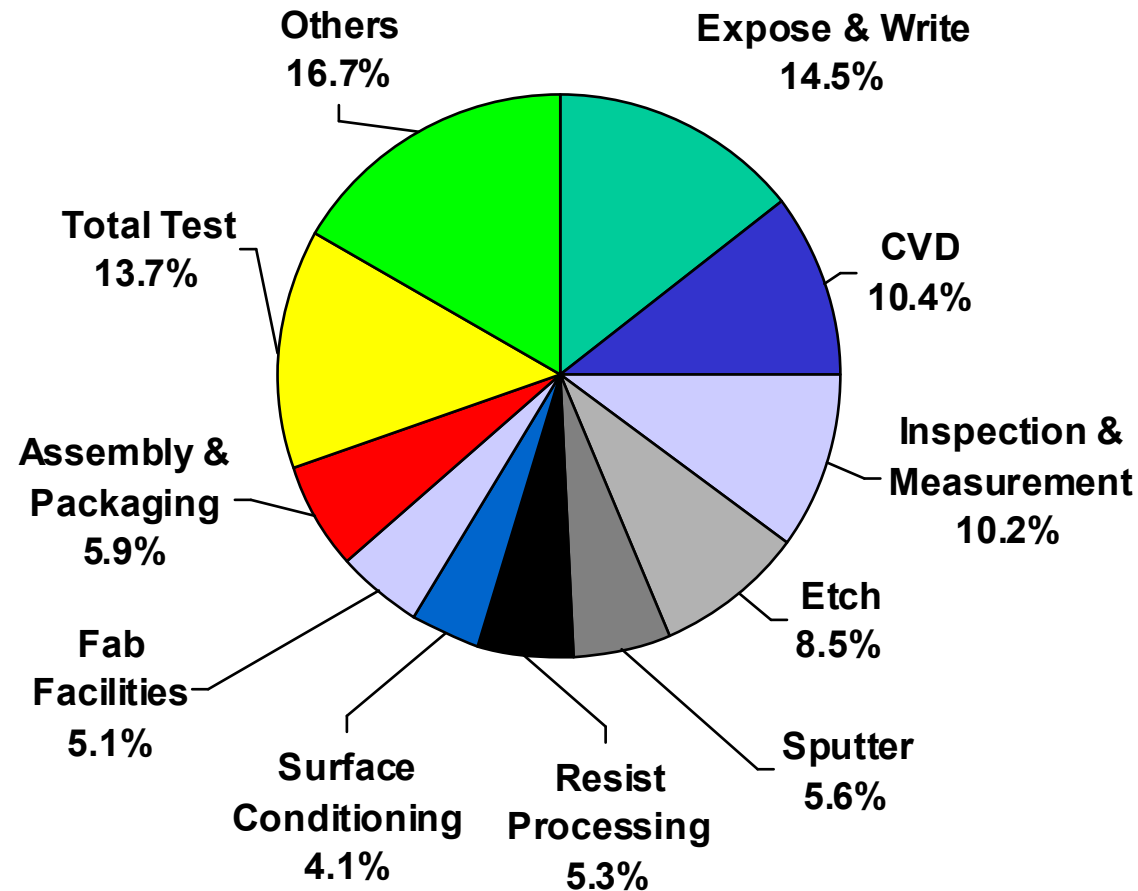


Annual Growth % (line graph)

Source: SEMI and SEMI/SEAJ year end historical reports



2002 Global Equipment Markets



Worldwide 2002 Billings = \$19.75B

Source: SEMI/SEAJ March 2003



Emerging Technologies Summary

Selected Emerging Technologies Summary	
Substrates	Silicon on insulator (SOI) & derivatives, strained silicon, strained SOI, 300 mm
Lithography	Lower cost photomasks, 2nd generation 193 nm resists and ancillaries, immersion lithography , 157 nm resists and ancillaries, NGL resists and ancillaries
Interconnects	Advanced copper electro plating solutions, hybrid low k materials, high k materials, spin on versus CVD, dielectric cleaning solutions, low k compatible CMP slurries
Package Materials	Green molding compounds, dielectric materials, overcoat materials, back coat materials, solder stems and balls

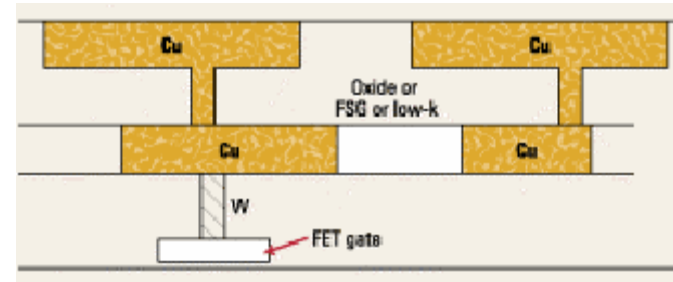


Multiple “winning” solutions for given technology node creates challenge and opportunity

Interconnect Integration Challenges

❑ Copper Interconnects

- “Single batch” ECP tools for 65 nm
- Electroplating chemistries becoming more complex



❑ Dielectrics

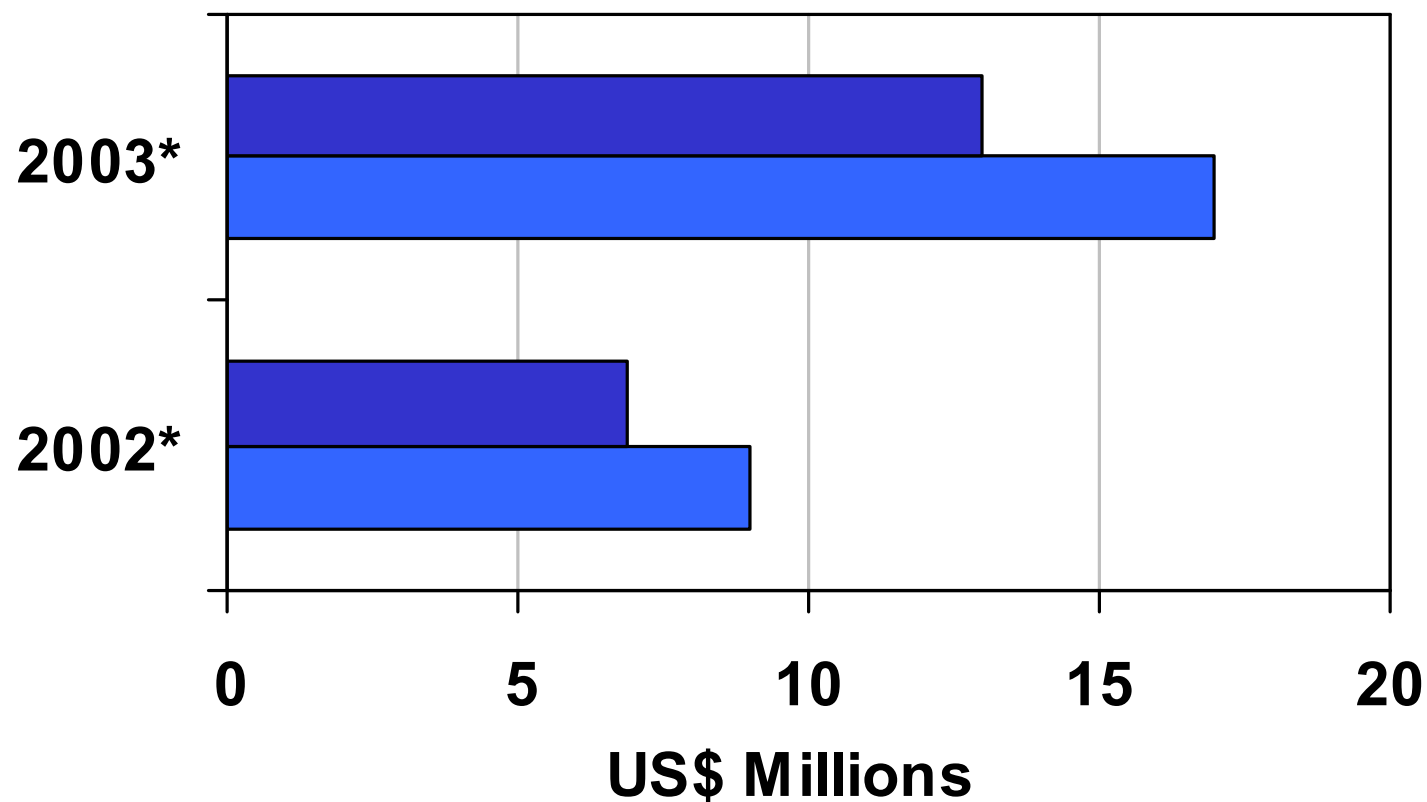
- Hybrid low k approach for inter metal dielectric
- Spin on versus chemical vapor deposition
- Hafnium based high k materials for gate insulator
- Metal gates

❑ Chemical Mechanical Planarization

- Low k compatible slurries
- Nanotechnology for slurries
- Post CMP Cleaning solutions

Source: Semiconductor International (image)

Electroplating Chemicals

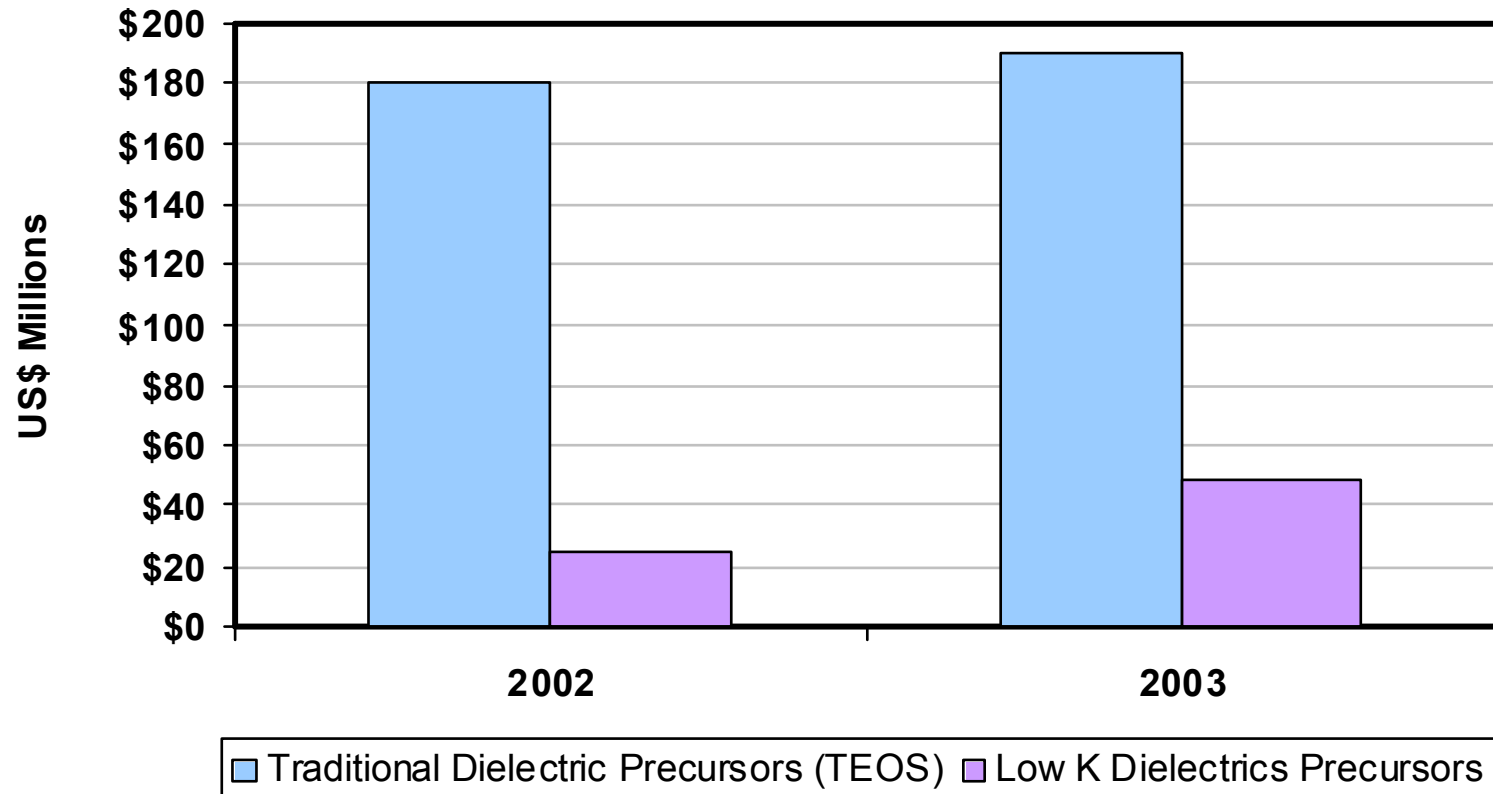


* High and low estimates due to significant volume of custom chemicals at some large customers

Source: Techcet Group March 2003



Dielectric Materials

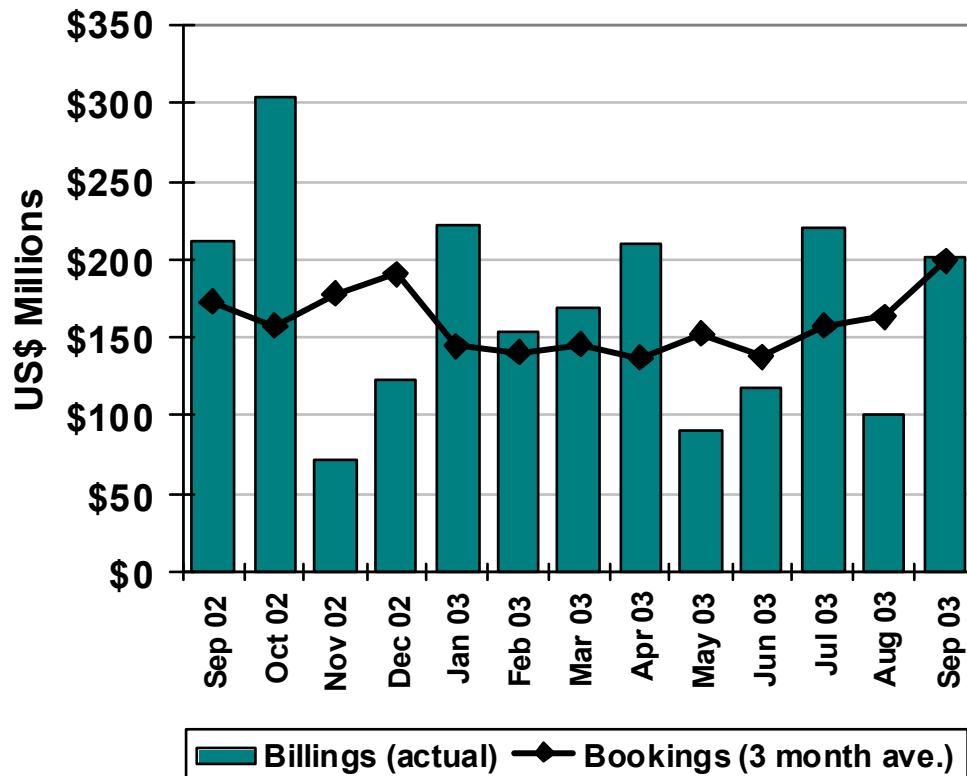


Source: Techcet Group May 2003, Kline & Company 2002



Chemical Vapor Deposition Trends

Worldwide CVD Equipment



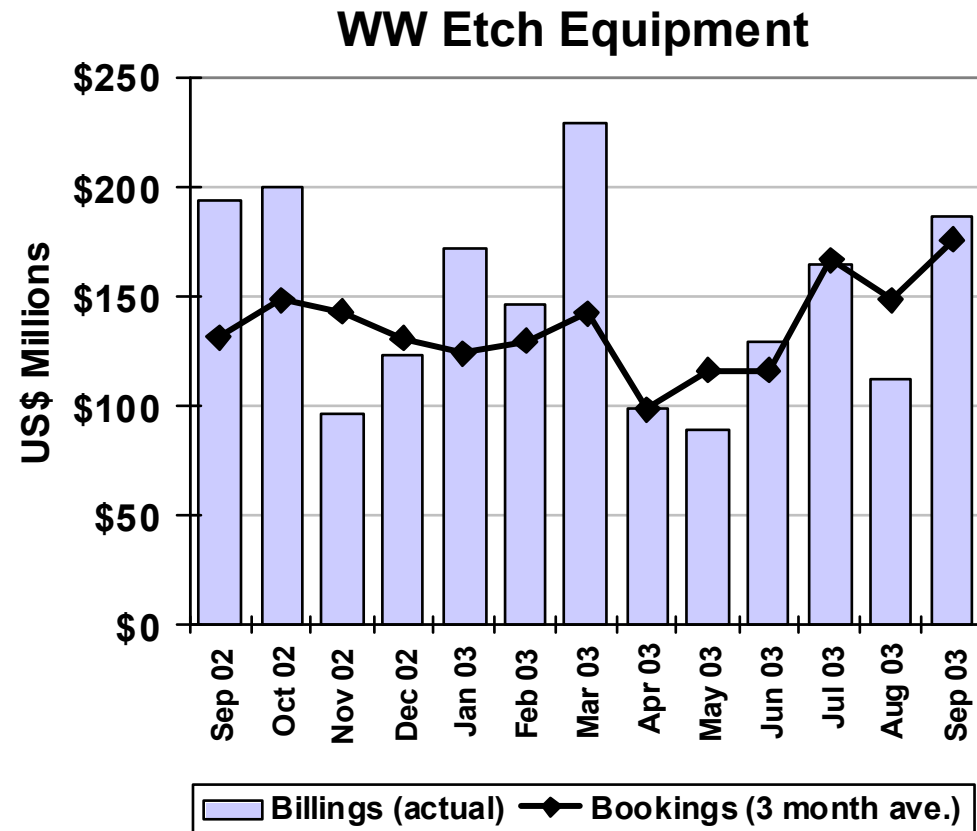
- ❑ September bookings grew 22% over August
- ❑ Low & high k films, dielectric anti-reflective coatings (DARC) and 300 mm offer growth opportunities
- ❑ Atomic layer deposition required for certain applications at 90 nm node
- ❑ Reduced pressure epitaxial reactors for heterostructures

Source: SEMI/SEAJ November 2003



Etch Equipment Trends

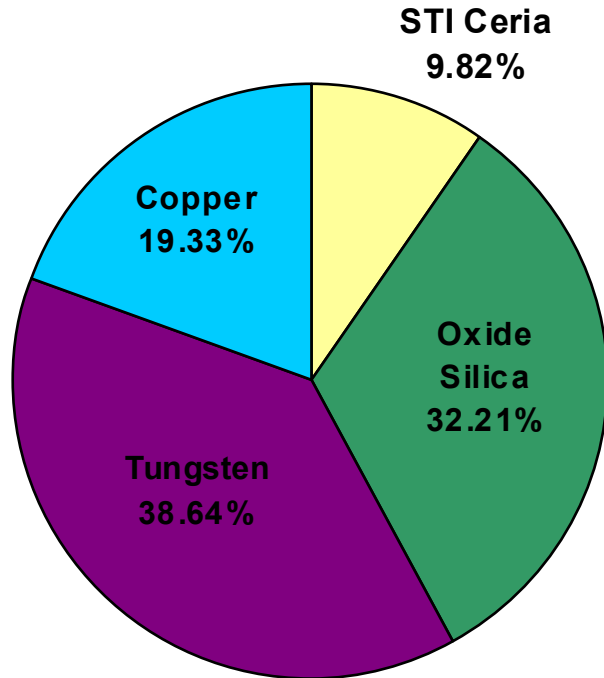
- ❑ September bookings grew 19% over August bookings
- ❑ Japan is largest market, closely followed by U.S. and Korea, respectively, through September 2003
- ❑ Dielectric etch tools represent largest market segment, followed by polysilicon and metal etch
- ❑ Technology and productivity improvements driving growth in dielectric etch tools



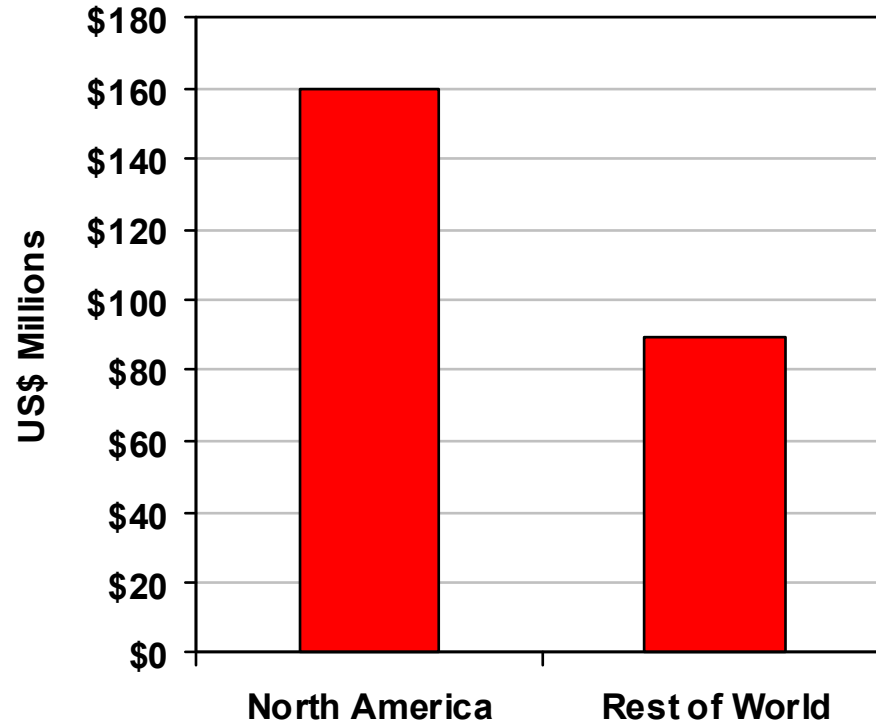
Source: SEMI/SEAJ November 2003



CMP Consumables



**2003 WW CMP Slurry
Market Estimate ~\$350M**



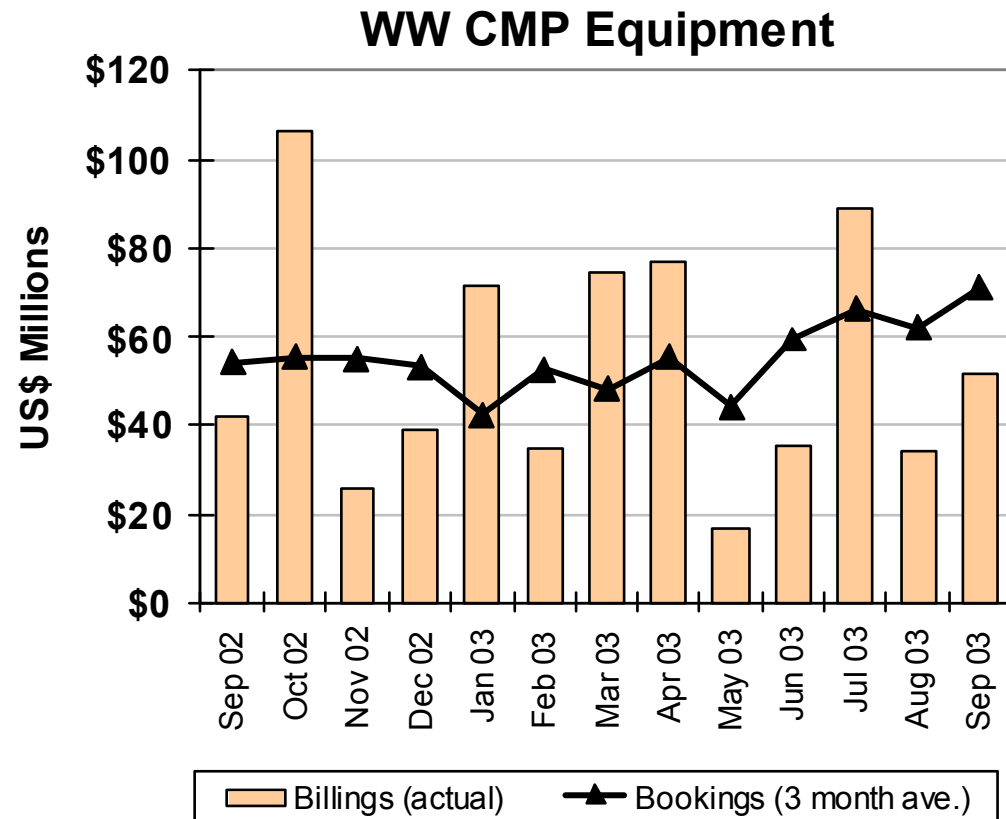
**2003 WW CMP Pad
Market Estimate ~\$250M**

Source: Techcet Group May 2003



CMP Equipment Trends

- ❑ September bookings up 15% over August bookings
- ❑ Taiwan demand for CMP tools only 11% of market in 2003, down from 25% in 2002
- ❑ Applied Materials, Ebara and Novellus Systems and Lam Research account for ~90% market



Source: SEMI/SEAJ November 2003



Changing Industry Dynamics

□ Proliferation of Joint Development Agreements

- Integration mandating closer cooperation
- Equipment suppliers moving into materials arena?
- Consortium for Advanced Semiconductor Materials & Related Technologies

□ New Entrants in Emerging Materials Segments

- CMP slurries and pads
- Dielectrics

□ Consolidation of Players

- Expanding product portfolios
- Powerhouses emerging

Summary

□ Numerous challenges and opportunities in materials and equipment markets

- Adoption of technologies at different nodes leads to slower market penetration for emerging materials and technologies
- Integration requires increased collaboration and increased R&D

□ Materials markets less cyclical than equipment markets

- Large investments required for infrastructure and R&D
- Variety of supply changes anticipated